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PATENT

Attorney Docket No. WPG-001
(10003/2)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS:	Chang et al.	CONFIRMATION NO.:	4380
SERIAL NO.:	10/715,743	GROUP NO.:	2829
FILING DATE:	November 17, 2003	EXAMINER:	A. Sarkar
TITLE:	Method for Fabricating Nanometer Gate in Semiconductor Device Using Thermally Reflowed Resist Technology		

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT AND RESPONSE

Sir:

This paper is respectfully submitted in response to an Office Action mailed from the U.S. Patent and Trademark Office on August 23, 2004. Applicants respectfully request entry of this Amendment and Response prior to further examination of the pending application.

Enclosed is a Petition for a two-month extension of time and a check in the required amount. As such, the period for response is extended up to and includes January 24, 2005 (January 23, 2005 being a Sunday). If any other extension period or fee is required for entry of this Amendment and Response, please consider this paper to be a conditional petition for the required extension of time and a conditional authorization to charge deposit account number 20-0531 for any such fee due.

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims begin on page 3 of this paper.

Remarks begin on page 6 of this paper.